EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2889	(702/57,58,109,110,117,118,119).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:57
L2	438	(324/718,716).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:57
L4	750	(438/18).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:57
L5	946	(700/109,110).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:58
L6	18	(calculat$3 manipulat$3) with (semiconductor$1 wafer$1 structure$1 wafer$1) with (goodness with fit$3)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 15:58
L7	7540	(wafer$1 chuck$1 workpiece$1) with (detect$3 monitor$3) with (defect$3 anomal$3 error$1 fault$3 fail$3)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 15:59

L8	163	test$3 with condition$3 with (temperatur$3 with intensity)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 15:59
L9	0	(curve near fltt$3) and (process$3 with (control $3 monitorS3)) and (detect$3 with defect$1) and ((goodness nearl (fitS4 measur$3)) (coefficient$1 near correlation$1)) and (sheet$1 near (resistance resistivity))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:00
L10	0	(((wafer$1 near defect$1)with (screen$3 monitor $3)) and (statistic$3 with process$3 with control $3) and (ATE with testers)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:01
L11	0	(wafer$1 with tester$1) same (process$3 with evaluat$3) same (statistic$3 with (fit$3 best$1flt $3))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:01
L12	7	("4031370" | "4905170").PN. OR ("5796983"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:01
L13	2	(1 2 4 5) and 6	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:02
L14	18	("4855253" | "5717490" | "5739909" | "5835225" | "6015718" | "6072191" | "6146910" | "6263255" | "6297880" | "6298470" | "6309900" | "6347291" | "6484064").PN. OR ("6743646").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:02

L15	8	(wafer$1 with tester$1) same (process$3 with evaluat$3) same screen$3 and (control$3 with process$3)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:02
L16	48	(curve near fitt$3) and (process$3 with (control$3 monitor$3)) and (detect$3 with defect$1) and ((goodness nearl (fit$4 measur$3)) (coefficient$1 near correlation$1)) and (sheet$1 near (resistance resistivity))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:03
L17	0	(wafer$1 with tester$1) same (process$3 with evaluat$3) same (statistic$3 with (fit$3 GOF best$1fit$3))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:04
L18	0	(((manipulat$5 calculat$5 form$3) with (goodness near1 (fit$3 measur$4 statistical $3))) and ((semiconductor$1 wafer$1) with (form$3 near process$3)) and (independent with variable$1)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:04
L19	19	(test$3 with structur$3) and (wafer$1 chuck$1 with workpiece$1) and (defect$3 with monitor$3) and ((goodness with fit$3) (curve$1 with fit$3))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:05
L20	1	(structure with test$3 with parameter$1) and ((measur$3 with monitor$3) with value$1) and (goodness with fit$3 with differenc$3) and (value$1 with differenc$3)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:06
L21	5	(((histor$3 with value$1) same curve$1) and (goodness with fit$3) and ((control$3 with limit $3) (threshold with value$1) (referenc$3 with value$1))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:06

L22	0	(12 4 5) and 20	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
L23	7	(12 4 5) and 12	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
L24	0	23 and 14	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
L25	0	23 and 8	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
L26	2	(fit$3 with curve$1 with value$1) and ((wafer$1 chuck$1 workpiece$1 substrat$3 structure$1) with monitor$3 with defect$3)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:08
L27	0	(fit$3 with curve$1 with value$1) and ((wafer$1 chuck$1 workpiece$1 substrat$3 structure$1) with monitor$3 with defect$3) and (compar$3 with ((referenc$3 threshold) with value$1))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:08
L28	204	(wafer$1 chuck$1 workpiece$1) with (detect$3 monitor$3) with (defect$3 anomal$3 error$1 fault$3 fail$3) and (fit$3 with (curv$3 graph$3 plot$3))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:08

L29	2	("5345392" | "6968291").PN. OR ("7081823").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:09
L30	30	("4933887" | "4944590" | "4950990" | "4965451" | "5020920" | "5047713" | "5099441").PN. OR ("5667300").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:09
L32	0	((((manipulat$5 calculat$5 form$3) with (goodness near1 (fitS3 measur$4 statistical $3))) and ((semiconductorS1 waferS1) with (form$3 near process$3)) and (independent with variable$1)).clm.	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:11
L33	0	32 and (1 2 4 5)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:11
L34	1	(monitor$3 with (process$3 near stability)) and (fit$3 with value$1) and (linear$3 with regression$3) and (coefficient$1 near (relat$3 correlat$3))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:11
L35	1	(monitor$3 with (process$3 near stability)) and (fit$3 with value$1) and (linear$3 with regression$3) and (coefficient$1 near (relat$3 correlat$3)) and (resist$3 with measur$3) and (effect$3 with (length$1 width))	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:12
L36	1	(monitor$3 with (process$3 near stability)) and (fit$3 with value$1) and (linear$3 with regression$3) and (coefficient$1 near (relat$3 correlat$3)) and (resist$3 with measur$3) and ((effect$3 with (length$1 width)) same wafer$1)	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:12

L37	0	((monitor$3 with (process$3 near stability)) and (fit$3 with value$1) and (linear$3 with regression$3) and (coefficient$1 near (relat$3 correlat$3)) and (resist$3 with measur$3) and ((effect$3 with (length$1 width)) same wafer $1)).clm.	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:13
L38	0	(1 2 4 5) and 36	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:13
L39	0	(1 2 4 5) and 37	US-PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:13

7/4/2008 4:13:37 PM

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